

INFORMATION CITED BY APPLICANTS THAT MAY BE MATERIAL TO THE PROSECUTION OF THE SUBJECT APPLICATION

pplicants:

N.B. Cobb et al.

Attorney Docket No. MEGC121796

Application No.: 10/698,596

Group Art Unit: 1756 2815

Filed:

October 31, 2003

Title:

SITE CONTROL FOR OPC

U.S. PATENT DOCUMENTS

*Examine			Kind	Date	•
<u>Initials</u>	No.	Document No.	Code	(mm/dd/yyyy)	Name
_K	_ U1	4,762,396		08/09/1988	Dumant et al.
	_ U2 ·	5,502,654		03/26/1996	Sawahata
	_ U3	5,655,110		08/05/1997	Krivokapic et al.
	_ U4	5,723,233	•	03/03/1998	Garza et al.
	_ U5	5,825,647		10/20/1998	Tsudaka
<u> </u>	_ U6	5,879,844		03/09/1999	Yamamoto et al.
	_ U7	6,016,357		01/18/2000	Neary et al.
	_ U8	6,049,660		04/11/2000	Ahn et al.
	_ U9	6,077,310		06/20/2000	Yamamoto et al.
	_U10	6,120,952		09/19/2000	Pierrat et al.
	U11	6,128,067		10/03/2000	Hashimoto
	U12	6,187,483	B1	02/13/2001	Capodieci et al.
	U13	6,243,855	B1	06/05/2001	Kobayashi et al.
	U14	6,249,904	B 1	06/19/2001	Cobb
	U15	6,263,299	B 1	07/17/2001	Aleshin et al.
	U16	6,269,472	B1	07/31/2001	Garza et al.
	U17	6,301,697 .	B1	10/09/2001	Cobb
	U18	6,370,679	Bl	04/09/2002	Chang et al.
·	U19	6,425,117	B1	07/23/2002	Pasch et al.
<u> VS</u>	U20	6,453,452	B1	09/17/2002	Chang et al.

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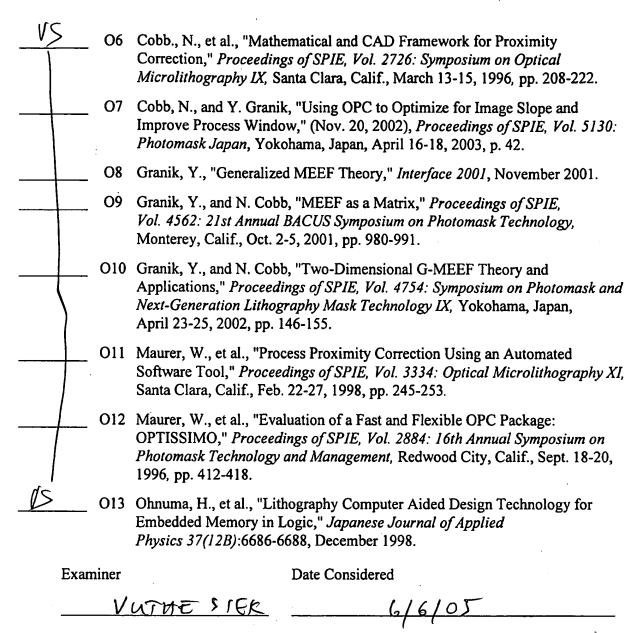
15_	U21	6,453,457	B1	09/17/2002	Pierrat et al.
<u>VS</u>	U22	6,467,076	B1	10/15/2002	Cobb
<u>vs.</u>	_ U23	6,499,003	B2	12/24/2002	Jones et al.

FOREIGN PATENT DOCUMENTS

*Examiner Cite			Kind	Publication Date		English	
Initial	No.	Document No.	Code	(mm/dd/yyyy)	Country	Abstract Translation Provided Provided	
15	F1	09319067	A	12/12/1997	JP	. X	
<u>√</u>	F2	WO 01/65315	A2	09/07/2001	wo		

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Initial	Cite No.	
5	O1	Cobb, N., and Y. Granik, "Model-Based OPC Using the MEEF Matrix," Proceedings of SPIE, Vol. 4889: 22nd Annual BACUS Symposium on Photomask Technology, Monterey, Calif., Sept. 30-Oct. 4, 2002, p.147.
+	O2	Cobb, N., and A. Zakhor, "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model," <i>Proceedings of SPIE, Vol. 3051: Symposium on Optical Microlithography X</i> , Santa Clara, Calif., Mar. 10-14, 1997, pp. 458-468.
-	O3	Cobb, N., and A. Zakhor, "Fast, Low-Complexity Mask Design," <i>Proceedings of SPIE, Vol. 2440: Symposium on Optical/Laser Microlithography VIII</i> , Santa Clara, Calif., Feb. 22-24, 1995, pp. 313-327.
	04	Cobb, N., and A. Zakhor, "Fast Sparse Aerial Image Calculation for OPC," Proceedings of SPIE, Vol. 2621: 15th Annual BACUS Symposium on Photomask Technology and Management, Santa Clara, Calif., Sept. 20-22, 1995, pp. 534-545.
	O5	Cobb, N., and A. Zakhor, "Large Area Phase-Shift Mask Design," <i>Proceedings of SPIE, Vol. 2197: Symposium on Optical/Laser Microlithography VII</i> , San Jose, Calif., March 2-4, 1994, pp. 348-360.



*Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

RCT:pt